

Applicant : Helmut Wurzer et al.  
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Page : 4

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IN THE ABSTRACT:

Please replace the abstract with the following version:

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AM A method of fabricating a barrier layer includes oxidizing a silicon-containing substrate to form a substrate oxide layer on the surface of the substrate, producing an oxygen-impervious layer at an interface between the substrate oxide layer and the substrate, and etching the substrate oxide layer until the underlying oxygen-impervious layer is uncovered.

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